

UNITED STATES PATENT AND TRADEMARK OFFICE

BEFORE THE PATENT TRIAL AND APPEAL BOARD

GlobalFoundries U.S. Inc.

Petitioner

v.

Godo Kaisha IP Bridge 1

Patent Owner

CASE IPR: *IPR2017-00920*

**PETITION FOR INTER PARTES REVIEW
OF UNITED STATES PATENT NO. 6,538,324**

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LIST OF EXHIBITS

- Exhibit 1001: U.S. Patent No. 6,538,324 to Tagami et al.
- Exhibit 1002: File History of U.S. Patent No. 6,538,324.
- Exhibit 1003: Expert Declaration of Dr. Sanjay Kumar Banerjee.
- Exhibit 1004: U.S. Patent No. 5,893,752 to Zhang et al.
- Exhibit 1005: U.S. Patent No. 6,887,353 to Ding et al.
- Exhibit 1006: Holloway et al., "Tantalum as a diffusion barrier between copper and silicon: Failure mechanism and effect of nitrogen additions," *Journal of Applied Physics*, 71(11), 5433-5444 (1992).
- Exhibit 1007: Sun et al., "Properties of reactively sputter-deposited Ta-N thin films," *Thin Solid Films*, 236 (1993) 347-351.
- Exhibit 1008: U.S. Patent No. 5,858,873 to Vitkavage et al.
- Exhibit 1009: U.S. Patent No. 5,668,411 to Hong et al.
- Exhibit 1010: Excerpt of El-Kareh, "Fundamentals of Semiconductor Processing Technologies," Kluwer Academic Publishers (1995).
- Exhibit 1011: Declaration of Dr. Li Jiang.
- Exhibit 1012: Library of Congress Catalog Record of Holloway et al., "Tantalum as a diffusion barrier between copper and silicon: Failure mechanism and effect of nitrogen additions," *Journal of Applied Physics*, 71(11), 5433-5444 (1992).
- Exhibit 1013: Library of Congress Catalog Record of Sun et al., "Properties of reactively sputter-deposited Ta-N thin films," *Thin Solid Films*, 236 (1993) 347-351.
- Exhibit 1014: Library of Congress Catalog Record of El-Kareh, "Fundamentals of Semiconductor Processing Technologies," Kluwer Academic Publishers (1995).
- Exhibit 1015: Stavrev et al., "Crystallographic and morphological characterization of reactively sputtered Ta, Ta-N and Ta-N-O thin films," *Thin Solid Films*, 307 (1997) 79-88.
- Exhibit 1016: Library of Congress Catalog Record of Stavrev et al., "Crystallographic and morphological characterization of reactively sputtered Ta, Ta-N and Ta-N-O thin films," *Thin Solid Films*, 307

(1997) 79-88.

- Exhibit 1017: Duan et al., "Magnetic Property and Microstructure Dependence of CoCrTa/Cr Media on Substrate Temperature and Bias," IEEE Transactions on Magnetics, Vol. 28, No. 5 (September 1992).
- Exhibit 1018: Library of Congress Catalog Record of Duan et al., "Magnetic Property and Microstructure Dependence of CoCrTa/Cr Media on Substrate Temperature and Bias," IEEE Transactions on Magnetics, Vol. 28, No. 5 (September 1992).
- Exhibit 1019: Moussavi et al., "Comparison of Barrier Materials and Deposition Processes for Copper Integration," Proceedings of the IEEE 1998 International Interconnect Technology Conference, pp. 295-97 (1998).
- Exhibit 1020: Library of Congress Catalog Record of Moussavi et al., "Comparison of Barrier Materials and Deposition Processes for Copper Integration," Proceedings of the IEEE 1998 International Interconnect Technology Conference, pp. 295-97 (1998).
- Exhibit 1021: Wijekoon et al., "Development of a Production Worthy Copper CMP Process," 1998 IEEE/SEMI Advanced Semiconductor Manufacturing Conference, pp. 354-63 (1998).
- Exhibit 1022: Library of Congress Catalog Record of Wijekoon et al., "Development of a Production Worthy Copper CMP Process," 1998 IEEE/SEMI Advanced Semiconductor Manufacturing Conference, pp. 354-63 (1998).
- Exhibit 1023: Wang et al., "Barrier Properties of Very Thin Ta and TaN layers Against Copper Diffusion," J. Electrochem. Soc., Vol. 145, No. 7, pp. 2538-45.
- Exhibit 1024: Library of Congress Catalog Record of Wang et al., "Barrier Properties of Very Thin Ta and TaN layers Against Copper Diffusion," J. Electrochem. Soc., Vol. 145, No. 7, pp. 2538-45.

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